

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

Claim 1 (original): A process for manufacturing gas diffusion electrodes, which process comprises:

- a) treating an area of a pre-shrunk porous hydrophobic substrate so as to restrict the slurry deposited in step b) to the said area
- 5 b) dispensing a slurry of catalyst onto the area,
- c) removing liquid from the dispensed slurry, and
- d) treating the dried slurry to remove organic materials.

Claim 2 (original): A process as in claim 1 wherein step a) comprises forming a well at the said area in the hydrophobic substrate.

Claim 3 (original): A process as in claim 1 where step a) comprises surface treating the hydrophobic substrate to render the substrate less hydrophobic in the said area.

Claim 4 (original): A process as in claim 1 wherein step a) comprises (i) forming a well in the pre-shrunk porous hydrophobic substrate and (ii) surface treating the hydrophobic substrate to render the substrate that is in the well or is destined to be within the well less hydrophobic.

Claim 5 (original): A process as in claim 4 wherein the surface treatment step reduces the hydrophobicity of the substrate only in the area of the substrate within the well or that is destined to form the well.

Claim 6 (currently amended): A process as claimed in claim 4 ~~or claim 5~~, wherein step i) is performed after step ii) or *vice versa*.

Claim 7 (currently amended): A process as claimed in ~~any of claims 1 to 6~~ claim 1, wherein step c) comprises heating the slurry to evaporate the liquid.

Claim 8 (currently amended): A process as claimed in ~~any one of claims 1 to 6~~ claim 1 wherein step d) comprises heating the dried slurry to a temperature sufficient to decompose the organic materials.

Claim 9 (currently amended): A process as in ~~any of claims 1 to 6~~ claim 1, where step c) is achieved by solidifying the liquid.

Claim 10 (currently amended): A process as claimed in claim ~~1 to 9~~, which includes pre-shrinking the hydrophobic substrate by heat treatment at a temperature greater than that used in either of steps c) or d).

Claim 11 (currently amended): A process as claimed in ~~any one of claims 1 to 10~~ claim 1, which includes a further step of :

- 5 e) cutting the catalyst deposit and the underlying portion of substrate from the rest of the hydrophobic substrate to provide a porous and conductive catalyst mass supported on the said portion of the substrate.

Claim 12 (currently amended): A process as claimed in ~~any one of claims 1 to 11~~ claim 1, wherein the hydrophobic substrate is PTFE.

Claim 13 (currently amended): A process as claimed in ~~any one of claims 1 to 12~~ claim 1 wherein steps (c) and (d) are performed in a single step.

Claim 14 (currently amended): A gas diffusion electrode made by the process of ~~any one of claims 1 to 13~~ claim 1.

Attorney Docket No. 4295-00018
Preliminary Amendment dated October 7, 2005

Claim 15 (new): A process as claimed in claim 5, wherein step i) is performed after step ii)
or *vice versa*.